

SECTION 4 SPECIFICATIONS

■ Applicable wafer size

5-, 6-, 8-inch

■ Microscope unit

Objectives	CF&IC EPI Plan, CF&IC EPI Plan Apo, CF&IC BD Plan, CF&IC BD Plan, Apo series
Eyepiece	CFUWL 10× (field number 25)
Optics	CF&IC
Illumination	12 V, 100 W, halogen lamp
Eyepiece tube	Triocular extension tilt eyepiece tube TL
Auto focus	LED illumination slit type AF
Revolving nosepiece	BD 5-hole motorized revolving nosepiece (Standard)
Option	Confocal microscope unit

■ Macro unit

Rotation	360°, endless
Tilt angle	0 ±30° each for X and Y axes
Operation	Automatic to preset values, or manual with joystick

■ Stage unit

Stage stroke	208 mm × 208 mm
Travel modes	<ul style="list-style-type: none"> ● Auto mode Automatic movement to recipe-programmed observation points (jump or scan) ● Manual mode Variable speed corresponding to joystick angle Low-speed travel corresponding to objective magnification ● Coordinate correction X and Y
Observation points	100 points per wafer inspection file (Up to 4000 inspection files)

■ **Wafer transport unit**

Number of elevators	Two or one
Elevator location	Front
Transport	Mechanical transport by vacuum suction Non-contact prealignment
Material of wafer suction area	PEEK (polyether-ether-ketone)

■ **Functions**

Sampling assignment	
GO/NG sort	
Online help	
Online operation (optional)	RC-232C or TCP/IP
Communication with host computer	Lot management and system management using GEM

■ **Environment**

Room temperature	23° ±3°C
Humidity	50% ±20%

■ **Utilities requirements**

Electricity	100 to 120 Va-c ±10%, 50/60 Hz, 14 A max., or 220 to 240 Va-c ±10%, 50/60 Hz, 7 A max.
Vacuum	≤ -80 KPa (-600 mmHg)

■ **Dimensions and weight**

Single-cassette type	995(W) × 1000(D) × 1380(H) mm; approx. 290 kg
Double-cassette type	1200(W) × 900(D) × 1380(H) mm; approx. 320 kg